

# PATENT ABSTRACTS OF JAPAN

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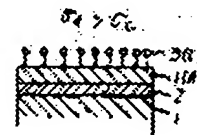
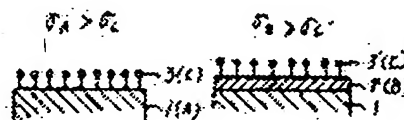
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## (54) PREPARATION OF MEMBRANE

### (57)Abstract:

**PURPOSE:** To form a controlled arbitrary atomic layer or molecular layer structure, in preparing the membrane utilized in an electronic device, by performing the growth of the membrane in the presence of an atomic group, wherein surface energy does not become larger than the energy of a growth surface, in the membrane growth surface.

**CONSTITUTION:** As third substances C, C', atomic groups or functional groups 3, 3' are chemical bonded to the atom of a growth surface or adsorbed thereby to make it possible to always keep the surface energies  $\sigma_C$ ,  $\sigma_{C'}$  of a formed membrane smaller than the energies  $\sigma_A$ ,  $\sigma_B$  of a substrate. Therefore, even through processes (a), (b), (c), all of films A, B can be always formed only of an arbitrary atomic layer as flat membranes. As a membrane forming stock material, a compound containing a membrane constituting element is pref. used and, as the stock compound, hydride, metal alkoxide or metal carboxide are pref.



## LEGAL STATUS

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